## Investigation of gate controllability in InGaAs/InAlAs double quantum wells towards the spin-filter application

GSIST Hokkaido Univ.<sup>1</sup>, NTT Device Technology Laboratories<sup>2</sup>, NTT Basic Research Laboratories<sup>3</sup>

<sup>O</sup>T. Yamashige<sup>1</sup>, A. Sawada<sup>1</sup>, S. Yokota<sup>1</sup>, H. Chen<sup>1</sup>, B. Liu<sup>1</sup> H. Sugiyama<sup>2</sup>, Y. Sekine<sup>3</sup> and T. Koga<sup>1</sup>

E-mail: yamashige@nano.ist.hokudai.ac.jp

In this study, we investigated the gate controllability of four samples of InGaAs/InAlAs double quantum well (DQW), where the doping densities are varied among samples (Table 1). The InGaAs/InAlAs DQW can be used for building a nonmagnetic spin-filter based on the Rashba effect<sup>[1]</sup>. The Rashba coefficient  $\alpha$  also varies from sample to sample since  $\alpha$ depends on the sheet career density<sup>[2]</sup>. When the potential profile of the DQW is globally symmetric about the middle barrier layer as shown in Fig. 1, only one spin component at the



Fig. 1 the potential profile of the DQW

Fermi energy [  $\mathbf{k} = (k_F, 0)$  ] can be put in the resonance level between the QW1 and QW2 by the applied gate voltage  $V_g$  or in-plane magnetic field  $B_y$ . For realizing the globally symmetric potential profile, it is inevitable to investigate the characteristic of each sample experimentally in addition to the design of heterostructures based on the Poisson- Schrödinger self-consistent solutions.

We measured Shubnikov-de Hass (SdH) oscillations at 1.5K with various  $V_{gs}$ . Then, we obtained the sheet career densities ( $N_{S1}$ ,  $N_{S2}$ ) associated with the first and the second subband level by the analyses of SdH data. In Fig. 2, we show the gate voltage ( $V_{g}$ ) dependence of the total sheet career density ( $N_{Stot}$ ) about one of our samples, IQE1-2, where  $N_{Stot} = N_{S1} + N_{S2}$ . We find that  $N_{Stot}$  is controlled by  $V_{g}$  as predicted theoretically. Only IQE1-2 among all the sample shows this ideal characteristic. We define the gate efficiency P as the ratio of the experimental gate capacitance to the theoretical one for the comparison among all the samples (Table 1).

## **References:**

[1] S. Souma, et al., arXiv; 1304. 6992 (2013).

[2] S. Faniel, et al., Phys. Rev. B 83; 115309 (2011).

	$n_1 \ ( imes 10^{24} m^{-3})$	$n_2 \ ( imes 10^{24} m^{-3})$	P (%)	α (× 10 <sup>-12</sup> eV•m)
KH3-5	4.0	4.5	91	4.22
IQE1-1	3.5	5.0	69	3.26
IQE1-2	2.5	4.0	100	2.18
KH4-4	3.5	5.0	63	3.41

Table 1  $n_1$  and  $n_2$  are the doping condition (see Fig. 1), *P* is the gate efficiency and  $\alpha$  is the Rashba coefficient of the investigated samples.



Fig. 2  $V_{\rm g}$  dependence of  $N_{\rm Stot}$